

Product Comparison

	IST RPX-540, -560	Competition (a Vapor Prime Oven)
Equipment Size:	27"x39"x76"	~46"x39"x45"
Chamber Dimension:	12"x20"x16" (-540) 16"x20"x17" (-560)	~ 16"x18"x16"
Chamber Material / Construction:	Structural T6061 Aluminum 100% Corrosion Proof	Welded 304 Stainless Steel
Temperature Uniformity:	± 1°C	± 3°C
Chamber Temperature:	RT to 140°C	~ near 200°C
Chamber Pressure Control:	10mt - 10Torr	100mt - 100Torr
Chemical Dispense:	Vaporization or Carrier Gas Assist metered by MFC	Mechanical Displacement Pump
Chemical Control Capability:	Partial Pressure control by capacitance manometer	Liquid Dispense Volume onto a Hot Plate
Precursors Capability:	Configurable from 1 to 5 precursors with Interchangeable Cartridges + 1 Gas Source Cartridges are RF-ID tagged for complete chemical traceability.	Up to 3 precursor bottles
Process Capability:	Silane & Metal Organics for ALD	Silanes
RF Plasma:	40kHz - 1000 Watts or 13.56MHz @ 600Watts or 13.56MHz (Pulse) @ 1000Watts	40KHz - 1000Watts
Loading Configurations:	Multi-Shelves, Wafer cassettes up to 300mm	Multi-Shelves, Wafer cassettes up to 300mm
Software / Control:	Windows-11 OS + Labview® Graphic Interface. Internet enabled. Remote monitoring and control available from anywhere in the world.	PLC
# of Process Recipes:	Only limited by disk space	up to 6
Power Requirements:	208V - 230VAC	208V - 230VAC